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(37 CFR 1.98(b))

APPLICANT  
**Aaron Scott Lukas, et al.**

FILING DATE 7/2/03

GROUP 1762**U.S. PATENT DOCUMENTS**

EXAMINER INITIALS	DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	5	4	5	4	9	1	5						
	6	0	4	2	9	9	4	3/28/2000	J. Yang, et al.	430	296	1/8/1999	
	6	0	5	4	2	0	6	4/25/2000	T. W. Mountsier	428	312.8	6/22/1998	
	6	2	3	8	7	5	1	5/29/2001	T. W. Mountsier	427	574	3/16/2000	
	6	2	8	4	0	5	0	9/4/2001	J. Shi, et al.	118	715	5/18/1998	
	6	3	1	2	7	9	3	11/6/2001	A. Grill, et al.	428	312.6	5/26/1999	
	6	4	7	5	9	3	0	11/5/2002	K. H. Junker, et al.	438	787	1/31/2000	
TS 9/17/08	2001-01	0	0	1	8	1	2	9	8/30/2001	A. Shiota, et al.	428	447	1/29/2001
	2001-01	0	0	3	8	9	1	9	11/8/2001	I. L. Berry, III, et al.	428	446	3/19/2001
	2002-02	0	1	0	2	4	1	3	8/1/2002	Q. Han, et al.	428	446	7/16/2001
2003-02	0	1	0	6	5	0	0	8/8/2002	R. Albano, et al.	428	304.4	9/14/2001	
	2003-02	0	0	3	2	3	0	0	2/13/2003	C. Waldried, et al.	438	725	5/14/2001
2003-03	0	0	5	4	1	1	5	3/20/2003	R. Albano, et al.	427	487	9/14/2001	

**FOREIGN PATENT DOCUMENTS**

EXAMINER INITIALS	DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES      NO
	EP	1	0	3	7	2	7	5	Sept-2002	Europe	Maeda et al.	X
	WO	0	0	0	2	2	4	1	Jan 2000	World	PCT	X
	WO	0	2	0	7	1	9	1	Jan 2002	World	PCT	X
	WO	02	0	6	5	5	3	4	Aug 2002	World	Pct	X

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

A. Hozumi, et al., "Low-Temperature Elimination of Organic Components from Mesostructured Organic-Inorganic Composite Films Using Vacuum Ultraviolet Light, Chem. Mater. 2000, 12, 3842-3847. no month

M. Ouyang, et al., "Conversion of Some Siloxane Polymers to Silicon Oxide by UV/Ozone Photochemical Processes, Chem Mater. 2000, 12, 1591-1596. (no month, but published on Web May 2000)

A. Hozumi, et al., "Micropatterned Silica Films with Ordered Nanopores Fabricated through Photocalcination, National Institute of Advanced Industrial Science & Technology, Volume 1, Number 8, August 2001.

T. Clark, Jr., et al., "A New Application of UV-Ozone Treatment in the Preparation of Substrate-Supported Mesoporous Thin Films, Chem Mater. 2000, 12, 3879-3884. no month, but pub on web - Dec. 2000

Q. Han, et al., "Ultra Low-k Porous Silicon Dioxide Films from a Plasma Process," IEEE (2001), pp. 171-173.

C. Waldried, et al., "Single Wafer RapidCuring™ of Porous Low-k Materials," IEEE (2002), pp. 226-228.

no month

EXAMINER Mark J. FagerDATE CONSIDERED 9/15/05

EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.